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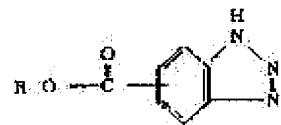
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(54) POSITIVE TYPE PHOTOSENSITIVE RESIN COMPOSITION

(57)Abstract:

PURPOSE: To enhance adhesion to a substrate and developability by incorporating one of carboxybenzotriazole derivatives in a positive type photoresist.

CONSTITUTION: The positive type photoresist resin composition is obtained by incorporating one of the carboxybenzotriazole derivatives represented by the formula shown on the right in which R is H or 1 to 3 C alkyl, in the positive type photoresist in an amount of 0.05 to 5 wt%, preferably, 0.2 to 2 wt% of the total solids of the photoresist. The resist pattern obtained by using this composition is extremely high in adhesion to the substrate, small in change and stable against time lapse, accordingly, floating up and peeling of the resist pattern from the substrate, intrusion of a metal plate, and the like are restrained from occurrence of them in the operation of etching, plating, and the like in the next processing stage.



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